

Appl. No. 10/710,395
Amdt. dated July 15, 2005
Reply to Office action of June 15, 2005

REMARKS/ARGUMENTS

1. Election/Restrictions:

Restriction to one of the following inventions is required under 35 U.S.C. 121:

5 I. Claim 1-10, drawn to a photoresist coating system, classified in class 118, subclass 52.

II. Claims 11-20, drawn to a method of performing a photolithography process, classified in class 427, subclass 240.

The inventions are distinct, each from the other because of the following reasons:

10 Inventions II and I are related as process and apparatus for its practice. The inventions are distinct if it can be shown that either: (1) the process as claimed can be practiced by another materially different apparatus or by hand, or (2) the apparatus as claimed can be used to practice another and materially different process. (MPEP 806.05(e)). In this case the apparatus can be used to perform a photoresist coating methods not requiring both the
15 steps of chilling and heating of the resist solution, for instance a method requiring only the step of chilling or heating the resist solution.

Because these inventions are distinct for the reasons given above and have acquired a separate status in the art as shown by their different classification, restriction for
20 examination purpose as indicated is proper.

Because these inventions are distinct for the reasons given above and have acquired a separate status in the art because of their recognized divergent subject matter, restriction for examination purposes as indicated is proper.

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Response:

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Applicant elects Claims 1-10 to restrict the inventions and to be required under 35 U.S.C. 121. Claims 11-20 are withdrawn to restrict for examination purposes as indicated. Claims 1-10 protectes the photoresist coating system and its components. Besides, in this case, the photoresist coating system can be used to perform a photoresist coating methods
5 not requiring both the steps of chilling and heating of the resist solution, for instance a method requiring only the step of chilling or heating the resist solution as examiner said.

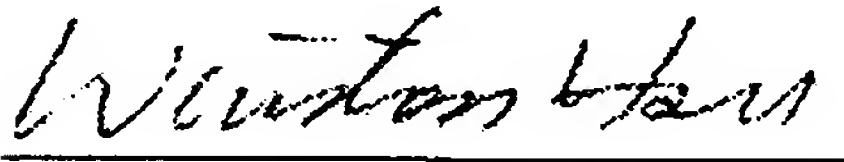
Claims 1-10 are also characterized by the specification and the figures. So, please consideration of claims 1-10 are politely requested.

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Applicant respectfully requests that a timely Notice of Allowance be issued in this case.

Sincerely yours,

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Date: July 15, 2005

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Note: Please leave a message in my voice mail if you need to talk to me. (The time in D.C. is 12 hours behind the Taiwan time, i.e. 9 AM in D.C. = 9 PM in Taiwan.)